

Sunday, June 8	Time	Monday, June 9	Time	Tuesday, June 10	Time	Wednesday, June 11	Time	Thursday, June 12	Time	Friday, June 13
Hike in the mountains/ by the seashore Sign up!	09:00-09:20	Opening	09:00-09:30	<b>Oxides &amp; Glasses</b>	09:00-09:30	<b>Nuclear Materials</b>	09:00-09:30	<b>Electronic excitations</b>	09:00-09:30	<b>Boundaries &amp; Interfaces</b>
	09:20-09:50	<b>New methods</b>	09:30-09:50	<b>I3 – J-M. Delaye</b>	09:30-09:50	<b>I5 – T. Jourdan</b>	09:30-09:50	<b>I6 – J. Kohanoff</b>	09:30-09:50	<b>I9 – W-S Lai</b>
		<b>I1 – K.A. Fichthorn</b>		O18 – K. Jolley		O31 – D. Terentyev		O41 – W. Weber		O58 – B. Uberuaga
	09:50-10:10	O1 – S. D. Kenny	09:50-10:10	O19 – A. Rivera	09:50-10:10	O32 – C. Barouh	09:50-10:10	O42 – M. Dapor	09:50-10:10	O59 – K. P. Boyle
	10:10-10:30	O2 – I. Martin-Bragado	10:10-10:30	O20 – A. Prada	10:10-10:30	O33 – L. Messina	10:10-10:30	O43 – P. de Vera	10:10-10:30	O60 – P. Zhang
	10:30-10:50	O3 – J-P. Crocombette	10:30-10:50	O21 – Peña-Rodríguez	10:30-10:50	O34 – L. Malerba	10:30-10:50	O44 – A. Wucher	10:30-10:50	O61 – C. L. Guerrero
	10:50-11:10	O4 – G. Hobler	10:50-11:10	O22 – V. Jansson	10:50-11:10	O35 – E. Martinez	10:50-11:10	O45 – R. Ullah	10:50-11:10	O62 – A. Suzuki
	11:10-11:30	Coffee break	11:10-11:30	Coffee break	11:10-11:30	Coffee break	11:10-11:30	Coffee break	11:10-11:30	Coffee break
	11:30-11:50	O5 – G. Martin	11:30-12:00	<b>Semiconductors</b>	11:30-11:50	O36 – Y. N. Liu	11:30-11:50	O46 – T. Apostolava	11:30-11:50	<b>Nanomaterials</b> O63 – E. Bringa
	11:50-12:10	O6 – H. Rouchette		<b>I4 – L. A. Marqués</b>	11:50-12:10	O37 – D. Nguyen-Manh	11:50-12:20	<b>Graphite &amp; SiC</b>	11:50-12:10	O64 – R. Garcia-Molina
	12:10-12:30	O7 – Z. Chang	12:00-12:20	O23 – L. Pizzagalli	12:10-12:30	O38 – P. Grigorev	12:20-12:40	<b>I7 – N. Marks</b>	12:10-12:30	O65 – K. Nordlund
	12:30-12:50	O8 – S. Fitzgerald	12:20-12:40	O24 – M. Prieto-Depedro	12:30-12:50	O39 – S. Jin		O47 – K. D. Krantzman	12:30-12:50	O66 – T-H Yen Vu
	12:50-13:10	O9 – R. Schaeublin	12:40-13:00	O25 – M. W. Ullah	12:50-13:10	O34 – M. Backman	12:40-13:00	O48 – P. Zhang	12:50-13:10	O67 – A. Bahm
	13:10-13:30	Lunch	13:00-13:20	Lunch	13:10-13:30	Lunch	13:00-13:20	Lunch	13:10-13:30	Closing
13:30-13:50	13:20-13:40		13:30-13:50		13:20-13:40					
13:50-14:10	13:40-14:00		13:50-14:10		13:40-14:00					
14:10-14:30	14:00-14:30		14:10-14:30		14:00-14:30					
Registration Open	14:30-15:00	<b>He &amp; H</b>	14:30-14:50	O26 – J. L. Gomez-Selles	14:30-14:50	<b>Excursion – Altea</b>	14:30-15:00	<b>Nuclear Waste &amp; Fuels</b>		
	15:00-15:20	<b>I2 – J. Marian</b>	14:50-15:10	<b>Surfaces</b> O27 – Y. Osetsky	14:50-15:10		<b>I8 – C. Stanek</b>			
		O10 – X. Gai	15:10-15:30	O28 – B. Weidtmann	15:10-15:30		O49 – P. Olsson			
	15:20-15:40	O11 – C. Ortiz	15:30-15:50	O29 – P. Phillip	15:30-15:50		O50 – S. T. Murphy			
	15:40-16:00	O12 – H-B Zhou	15:50-16:10	O30 – Z. Postawa	15:50-16:10		O51 – C. Scott			
	16:00-16:20	Coffee break	16:10-16:30	Coffee break	16:10-16:30		Coffee break			
	16:20-16:40	O13 – A. De Backer	16:30-16:50	<b>Poster Session</b>	16:30-16:50		O52 – P. A. Burr			
	16:40-17:00	O14 – F. Gao			16:50-17:10		O53 – T. Oda			
	17:00-17:20	O15 – C. Gonzalez	17:10-17:30	<b>V, Mo &amp; other metals</b> O54 – D. Xu	17:10-17:30		O55 – W. Hu			
	17:20-17:40	O16 – T. Yoshiie	17:30-17:50	O56 – A. B. Sivak	17:30-17:50		O57 – A. V. Korchuganov			
17:40-18:00	O17 – A. Milocco	17:50-18:10		17:50-18:10						
18:00-18:20		18:10-18:30		18:10-18:30						
Welcome reception at Melia	Banquet- VOLVO OCEAN RACE									

<b>POSTER SESSION</b>	<b>Tuesday June 10, 2014</b>		
<b>New methods</b>	<b>Nuclear Materials (W)</b>	<b>Oxides &amp; glasses</b>	<b>Boundaries &amp; Interfaces</b>
(P1) P. C. M. Fossati	(P21) G. Valles	(P38)	(P55) M-M. Peng
<b>Electronic excitations</b>		(P39) A. R. Paramo	(P56) P. Piaggi
(P2) M. Dapor	(P23) C. S. Becquart		<b>Nanomaterials</b>
(P3) L. Calliari	(P24) Li Min	(P41) S. T. Murphy	(P57) E. H. Ahlgren
(P4) I. Abril	(P25) X. Shu	<b>Nuclear Waste &amp; Fuels</b>	(P58) V. M. de Menezes
(P5) A. M. Tornero-López	<b>V, Mo &amp; other metals</b>	(P42) P. C. M. Fossati	(P59) C. Anders
(P6) A. A. Shukri	(P26) W. Xiao	(P43) P. Kowalski	(P60) S-i Satake
<b>Nuclear Materials (Steels)</b>	(P27) M. J. Caturla	(P44) J. Wiktor	(P61) C. Denton
(P7)	<b>He &amp; H</b>	<b>Surface effects</b>	(P62) S. Heredia-Avalos
(P8) A. Bakaev	(P28) E. Martinez	(P45) M. J. Aliaga	(P63) J. Martínez-Asencio
(P9) I. Dopico	(P29) L. Agudo	(P46) R. Smith	(P64) R. Webb
(P10)	(P30) J. Cui	(P47) S. Parviainen	
(P11) M. Posselt	(P31) J. L. Zhang	(P48) J. C. Jimenez-Saez	
(P12) M. Nagel	(P32) D. V. Bachurin	(P49) C. Anders	
(P13) E. Del Rio	(P33) M. A. Cerdeira	(P50) W. Moller	
(P14) F. Granberg	<b>Semiconductors</b>	(P51) C. Anders	
(P15) K. P. Zolnikov		(P52) P. Phillip	
(P16) K. Henriksson	(P35) P. Lopez	(P53) V. Jansson	
(P17) Y. Watanabe	<b>Graphite &amp; SiC</b>	(P54) R. A. Yankov	
(P18) A. Souidi	(P36) J. Liu		
(P19) A. Souidi	(P37) I. Martin-Bragado		
(P20) G. Adjanor			